## **EAST Search History**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	24768	((substrate or wafer) near4 (temperature or heat\$3)) with (measur\$5 or sens\$3 or detect\$3 or determin\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/26 12:20
L2	25407	(substrate or wafer) with (temperature or heat\$3) with ((dimension\$3 near response) or expan\$4 or deform\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/26 12:21
L3	9934	(substrate or wafer) with (temperature or heat\$3) with ((dimension\$3 near response) or expan\$4 or deform\$5) with (calculat\$3 or determin\$5 or predict\$3 or model\$3 or coefficient)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/26 12:24
L4	886	1 and 3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/26 12:25
L5	3848	(substrate or wafer) with ((dimension\$3 near response) or expan\$4 or deform\$5) with (correct\$3 or adjust\$4 or compensat\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/26 12:26
L6	124	4 and 5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/26 12:27
L7	186969	(mask or reticle or pattern\$3) and (\$6lithograph\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/26 12:28

## **EAST Search History**

PK-8/26/06